

<b>Notice of References Cited</b>	Application/Control No. 10/732,931	Applicant(s)/Patent Under Reexamination KIM ET AL.	
	Examiner Patricia A. George	Art Unit 1765	Page 1 of 1

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*	C	US-6,117,698	09-2000	Atobe et al.	438/21
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	K	US-			
	L	US-			
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Dobins (High Density Plasma Deposition of SiO <sub>2</sub> ; <a href="http://www.enigmatic-consulting.com/semiconductor_processing/CVD_Fundamentals/films/HDP_SiO2.html">http://www.enigmatic-consulting.com/semiconductor_processing/CVD_Fundamentals/films/HDP_SiO2.html</a> ) web page created March 2005
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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